Fabrication techniques for AI and AI alloy optical coatings for the GIMM



Baseline Fabrication: •Pure Al •Electroplated thick film •Smoothed by single point diamond turning (SPDT)

Too soft: •Plastic failure under laser testing •No mechanical polishing •"gummy" during machining



Potential Solutions: Advanced polishing •Smoother deposition •Harder alloy

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Chemical Mechanical Polishing beats Single Point Diamond Turning

Better prototype:

•Smoother surface with CMP •SPDT must cut deep; needs more deposition •No hardness requirement for CMP

Better production:

•One wobble in diamond point spoils a whole mirror •Time for CMP scales as depth removed; for SPDT, as area •CMP has history of semiconductor-level QC

Preliminary results:

•Good smoothness, but some trapped abrasive.

•Poor initial performance attributed to slurry particles.

Introduction to CMP:

•Porous polishing pad (yellow, below) •Slurry, with abrasive particles in a corrosive liquid

•Mirror (or wafer) held against polishing pad by carrier (gray). •Control of pressure, rotation rates, slurry flow

Load Pad rotation Carrier rotation Slurry: corrosive with abrasive Carrier Polishing pad: particles polyurethane foam



Work with Cabot

•SPDT first chosen for want of vendor to polish pure Al.

•Cabot Mircoelectronics has produced samples, and is improving the process.

•Can scale up to productionsized mirrors





Ideally,

- 2.Passivation limits material removal until surface layer is thinned by abrasion
- 3.Particles never break through passivating layer
- 4.Relative speed between pad & carrier is approximately equal at any point on the mirror



The irregular gray shape represents a work piece with a rough surface as it undergoes chemicalmechanical polishing



Chemical action: The slurry (white, with blue particles) corrodes the workpiece to form a softened layer (light blue). Diffusion limits its thickness.



Mechanical action: Abrasive particles (blue are pressed into the softened layer by the moving polishing pad (yellow), thinning the layer process is repeated at high points.



Chemical action, continued: The softened layer re-grows in the thinned areas, leaving a smoother surface. The continuously.





